IN THE CLAIMS:

The status of each claim that has been introduced in the above-referenced application is identified in the ensuing listing of the claims. This listing of the claims replaces all previously submitted claims listings.

Claims 1-14. (Cancelled)

15. (Currently Amended) A method for forming a mold gate of a tape substrate, comprising:

forming an aperture of the mold gate in a flexible dielectric film of the tape substrate; and concurrently patterning conductive lines and a support structure of the mold gate from the same conductive film, the support at least partially overlapping the aperture.

- 16. (Currently Amended) The method of claim 15, further comprising: securing said the conductive film to said the flexible dielectric film.
- 17. (Currently Amended) The method of claim 16, wherein said-securing the conductive film is effected before said-forming an aperture of the mold gate.
- 18. (Currently Amended) The method of claim 17, wherein said-forming an aperture comprises etching the flexible dielectric film.
- 19. (Currently Amended) The method of claim 18, wherein said etching the flexible dielectric film comprises at least one of wet etching and dry etching the flexible dielectric film.
- 20. (Currently Amended) The method of claim 16, wherein said-securing the conductive film is effected following said-forming an aperture of the mold gate.

- 21. (Currently Amended) The method of claim 20, wherein said-forming an aperture comprises mechanically removing material of the flexible dielectric film.
- 22. (Currently Amended) The method of claim 21, wherein said-mechanically removing material comprises die cutting the flexible dielectric film.
- 23. (Currently Amended) The method of claim 15, wherein said-concurrently patterning comprises: forming a mask over said-the conductive film; and removing material of said-the conductive film through apertures of said-the mask.
- 24. (Currently Amended) The method of claim 23, wherein said-removing material comprises etching said-the conductive film.
- 25. (Currently Amended) The method of claim 15, further comprising: coating sidewalls of said-the aperture with a material that reduces or prevents adhesion of a packaging material to the mold gate.

26.

providing a flexible dielectric film; forming an aperture of a mold gate in said-the flexible dielectric film; and substantially concurrently forming a support element of said-the mold gate and conductive traces from a single conductive film laminated onto a surface of said-the flexible dielectric film, the support structure at least partially overlapping the aperture.

(Currently Amended) A method for fabricating a tape substrate, comprising:

27. (Currently Amended) The method of claim 26, wherein said providing said the flexible dielectric film comprises providing said the flexible dielectric film with said the single conductive film prelaminated onto said the surface thereof.

- 28. (Currently Amended) The method of claim 26, wherein said-providing said-the flexible dielectric film comprises providing said-the flexible dielectric film without said-the single conductive film on said-the surface thereof.
- 29. (Currently Amended) The method of claim 28, further comprising: laminating said-the single conductive film onto said-the surface of said-the flexible dielectric film.
- 30. (Currently Amended) The method of claim 29, wherein said-laminating is effected following said-forming said-the aperture.
- 31. (Currently Amended) The method of claim 30, wherein said-forming said-the aperture comprises mechanically forming said-the aperture.
- 32. (Currently Amended) The method of claim 31, wherein said-mechanically forming said-the aperture comprises die cutting said-the flexible dielectric film.
- 33. (Currently Amended) The method of claim 26, wherein said-forming said-the aperture comprises mechanically forming said-the aperture.
- 34. (Currently Amended) The method of claim 33, wherein said-mechanically forming said-the aperture comprises die cutting said-the flexible dielectric film.
- 35. (Currently Amended) The method of claim 26, wherein said-forming said-the aperture comprises:

forming a mask on a surface of said-the flexible dielectric film; and removing material of said-the flexible dielectric film through apertures of said-the mask.

- 36. (Currently Amended) The method of claim 35 wherein said-removing comprises etching said-the material of said-the flexible dielectric film.
- 37. (Currently Amended) The method of claim 36, wherein said etching comprises at least one of dry etching and wet etching said the material of said the flexible dielectric film.
- 38. (Currently Amended) The method of claim 26, wherein said-forming said-the aperture is effected at a location which is external to an outer boundary of an area of said-the flexible dielectric film where a finished tape substrate is to be located.
- 39. (Currently Amended) The method of claim 26, wherein said-substantially concurrently forming comprises: forming a mask over said-the single conductive film; and removing material of said-the single conductive film through apertures of said-the mask.
- 40. (Currently Amended) The method of claim 39, wherein said-removing material comprises etching said-the single conductive film.
- 41. (Currently Amended) The method of claim 26, further comprising: coating sidewalls of said-the aperture with a material that reduces or prevents adhesion of a packaging material to said-the mold gate.
- 42. (Currently Amended) The method of claim 26, further comprising plating conductive structures of said-the support element.

Claims 43-50. (Cancelled)